



# **New research capabilities: He-3 Ion Beam Analysis System and Indentation of Tritiated Samples**

**J. A. Knapp,  
W. R. Wampler, J. C. Banks, and J. F. Browning  
Sandia National Laboratories**

**Working Group on the Physics and Chemistry of Metal Tritides  
October 13, 2004  
Albuquerque, NM**

Thanks to: J. E. Mikkalson, S. Van Deusen, E. Staab, and T. D. Kraus



Sandia is a multiprogram laboratory operated by Sandia Corporation, a Lockheed Martin Company,  
for the United States Department of Energy under contract DE-AC04-94AL85000.





# Two new capabilities for $^3\text{He}$ studies

---

## ◆ Multi-element ion beam analysis system

- Simultaneous, non-destructive profiling of H, D, T,  $^3\text{He}$ , O, and surface C.
- Unique system based on heavy ion Elastic Recoil Detection in building 884.
- Status: assembly underway

## ◆ Nanoindentation of tritiated films

- Mechanical property measurements for tritiated thin films.
- Containment procedures allow use of indenter in 884.
- Status: operational

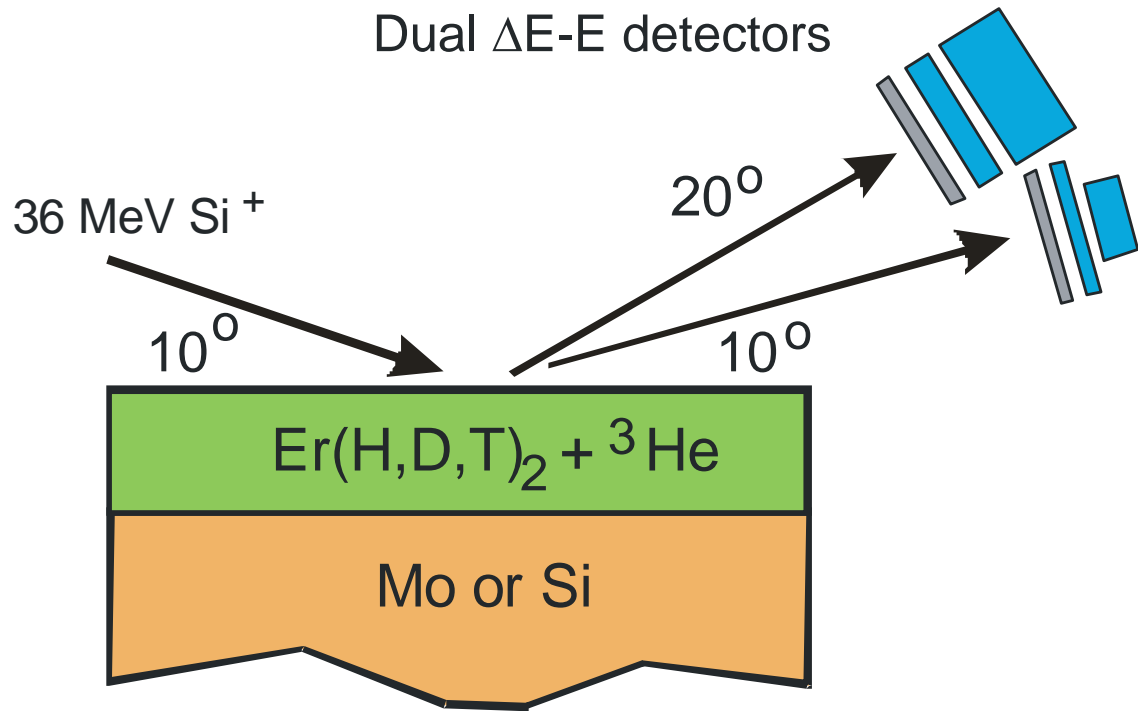


# New IBA system to study $^3\text{He}$ release

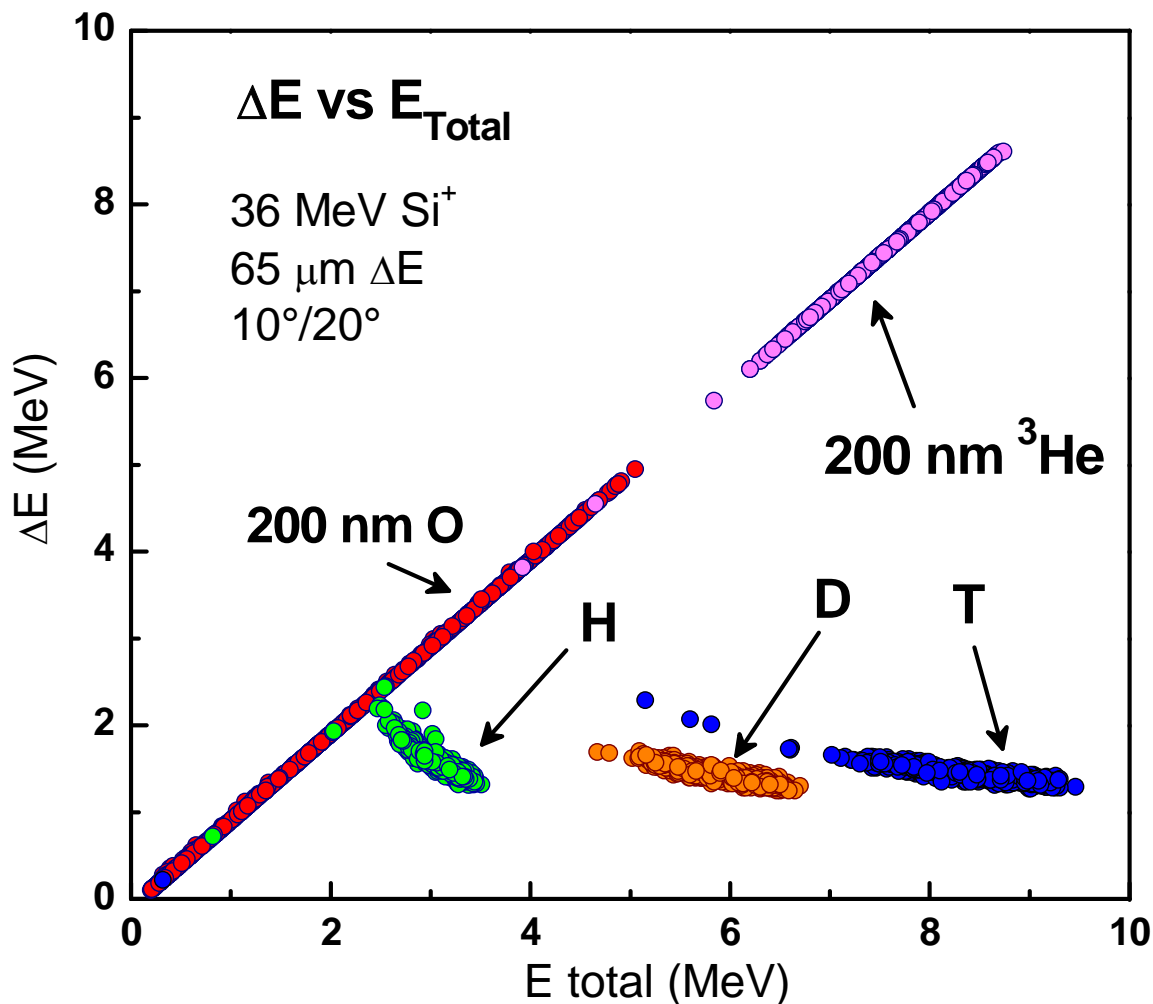
- ◆ Problem: profile light elements in Erbium Tritide films
  - Need to simultaneously analyze H, D, T,  $^3\text{He}$ , O, and surface C.
  - Existing HDT analysis chamber cannot measure  $^3\text{He}$  or measure O on a Si substrate.
  - New system detector configuration determined using extensive ion beam simulations.
- ◆ Applications:
  - Profile  $^3\text{He}$  and T to study “denuded” zone and early  $^3\text{He}$  release.
  - Study profile changes as films age. (technique is non-destructive).
  - Correlate film composition with fabrication parameters and mechanical properties.

# Analysis method

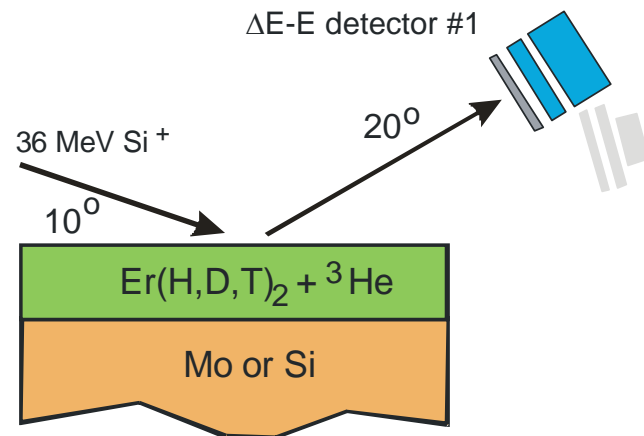
- Heavy ion elastic recoil detection (ERD) with 36 MeV Si<sup>+</sup> analysis beam
- Thick  $\Delta E$ -E detector at 20° to profile H, D, T, <sup>3</sup>He
- Thin  $\Delta E$ -E detector at 10° to profile O, C
- Each detector pair has a thin foil to block the Si analysis beam.



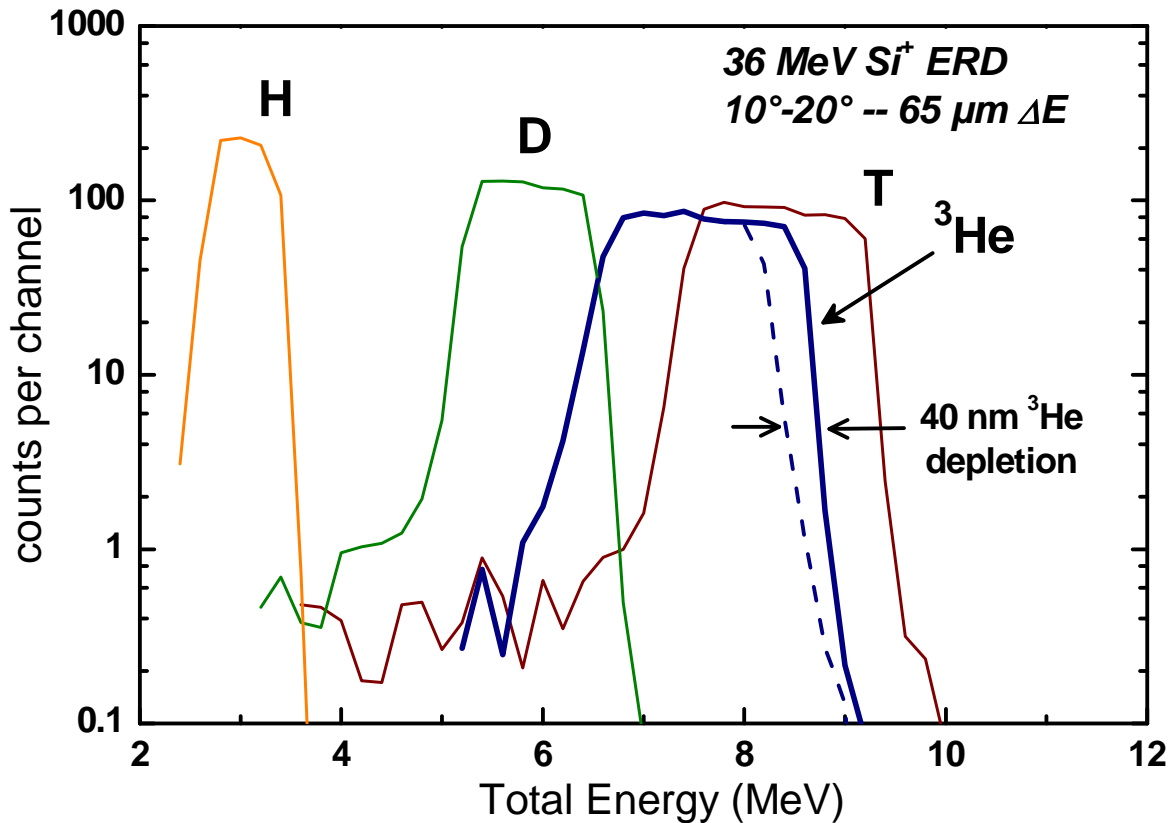
# $\Delta E$ -E detector at $10^\circ$ in, $20^\circ$ out



◆ Separates H, D, T and  $^3\text{He}$  from O

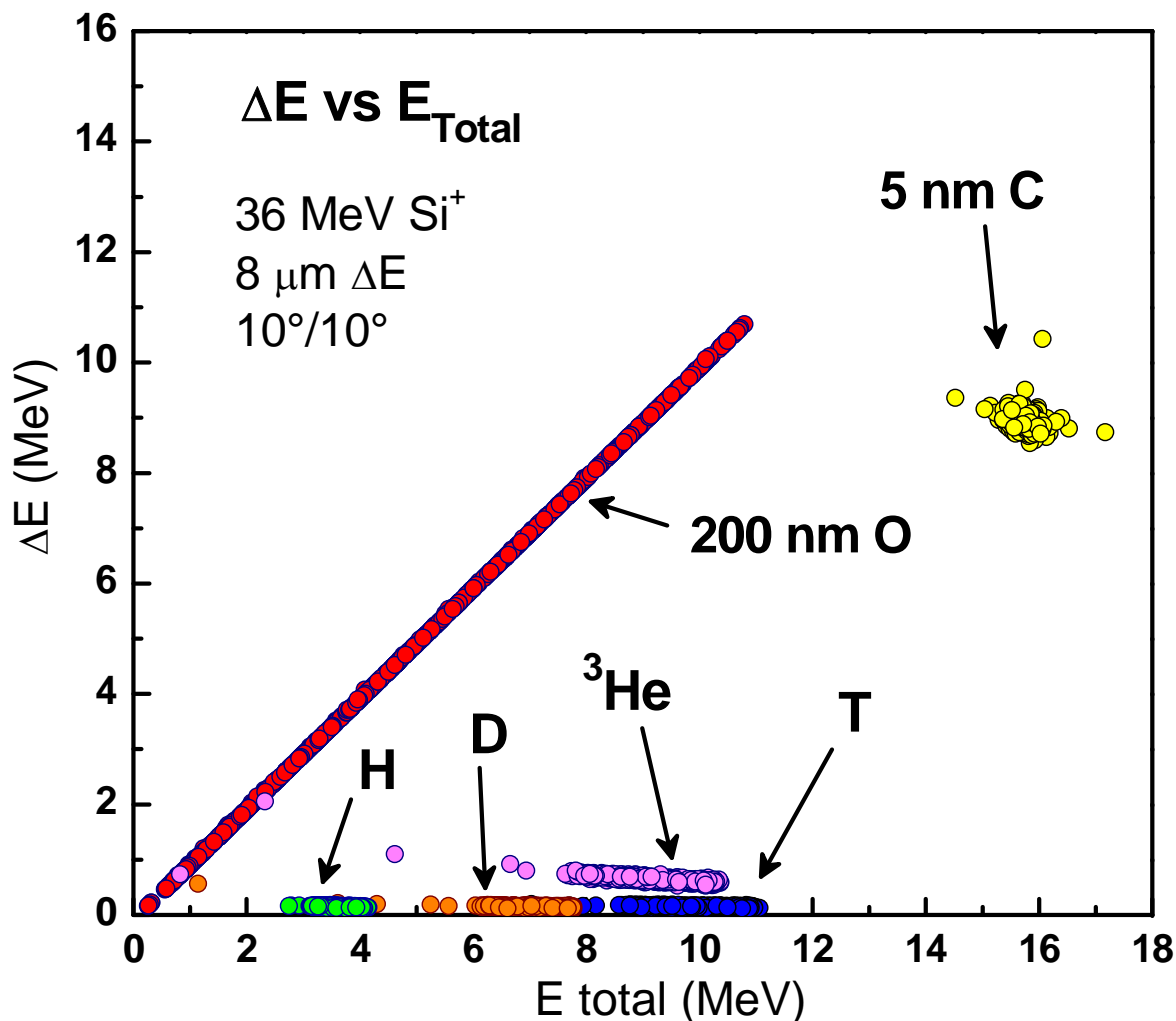


# Energy spectra - $\Delta E$ -E detector #1

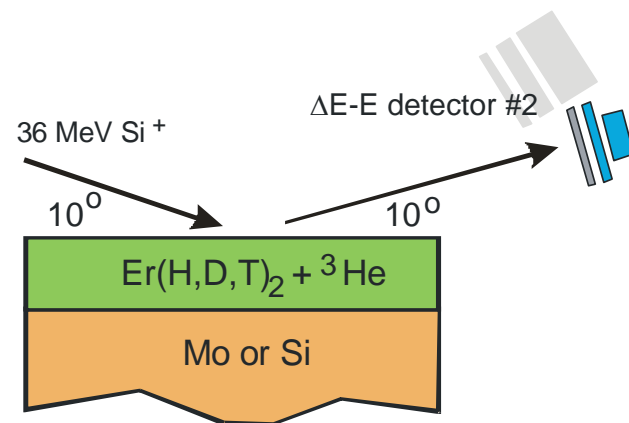


- **Sample:** 200 nm Er(H,D,T)<sub>2</sub> with 10% <sup>3</sup>He and 5% O
- 36 MeV Cl<sup>+</sup> beam incident at 10°, exit at 20°, 1.3 msr
- 65  $\mu\text{m}$   $\Delta E$
- 1x10<sup>5</sup> ion histories

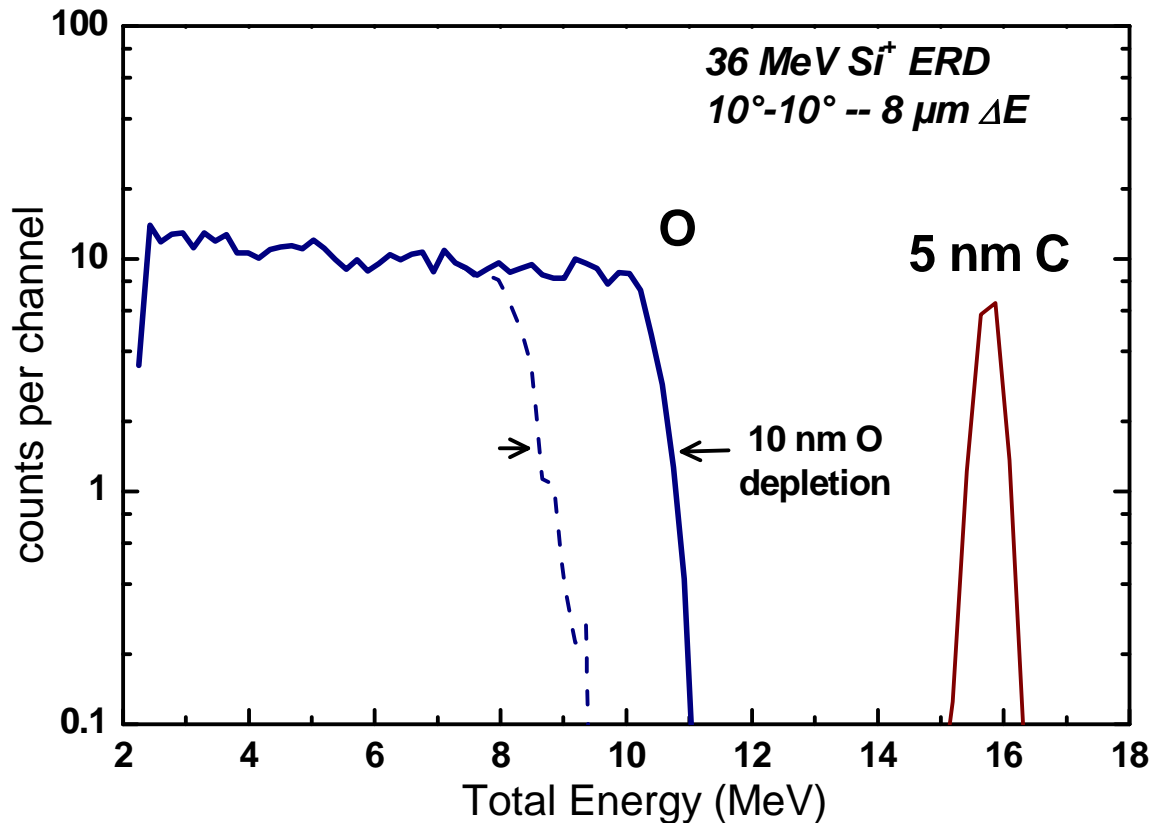
# $\Delta E$ -E detector at $10^\circ$ in, $10^\circ$ out



◆ Separates O and C from lighter elements.



# Energy spectra - $\Delta E$ -E detector #2



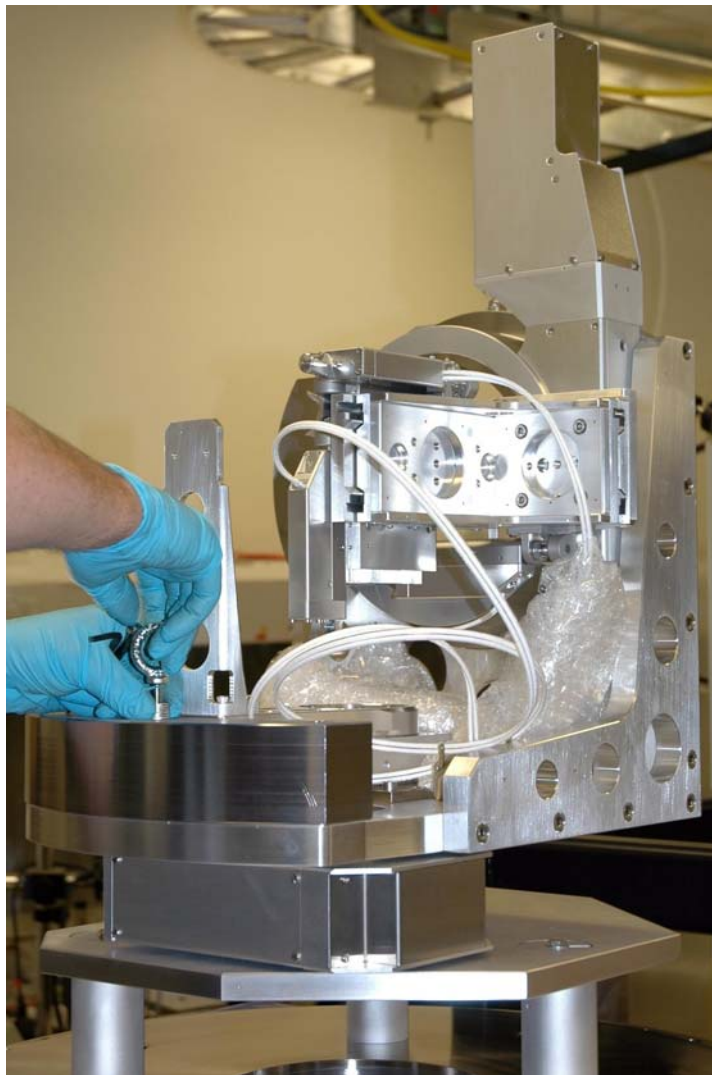
- Sample: 200 nm Er(H,D,T)<sub>2</sub> with 10% <sup>3</sup>He and 5% O, plus 5 nm surface C
- 36 MeV Cl<sup>+</sup> beam incident at 10°, exit at 10°, 1.3 msr
- 8  $\mu$ m  $\Delta E$  only
- 1x10<sup>5</sup> ion histories



# He-3 ion beam analysis system

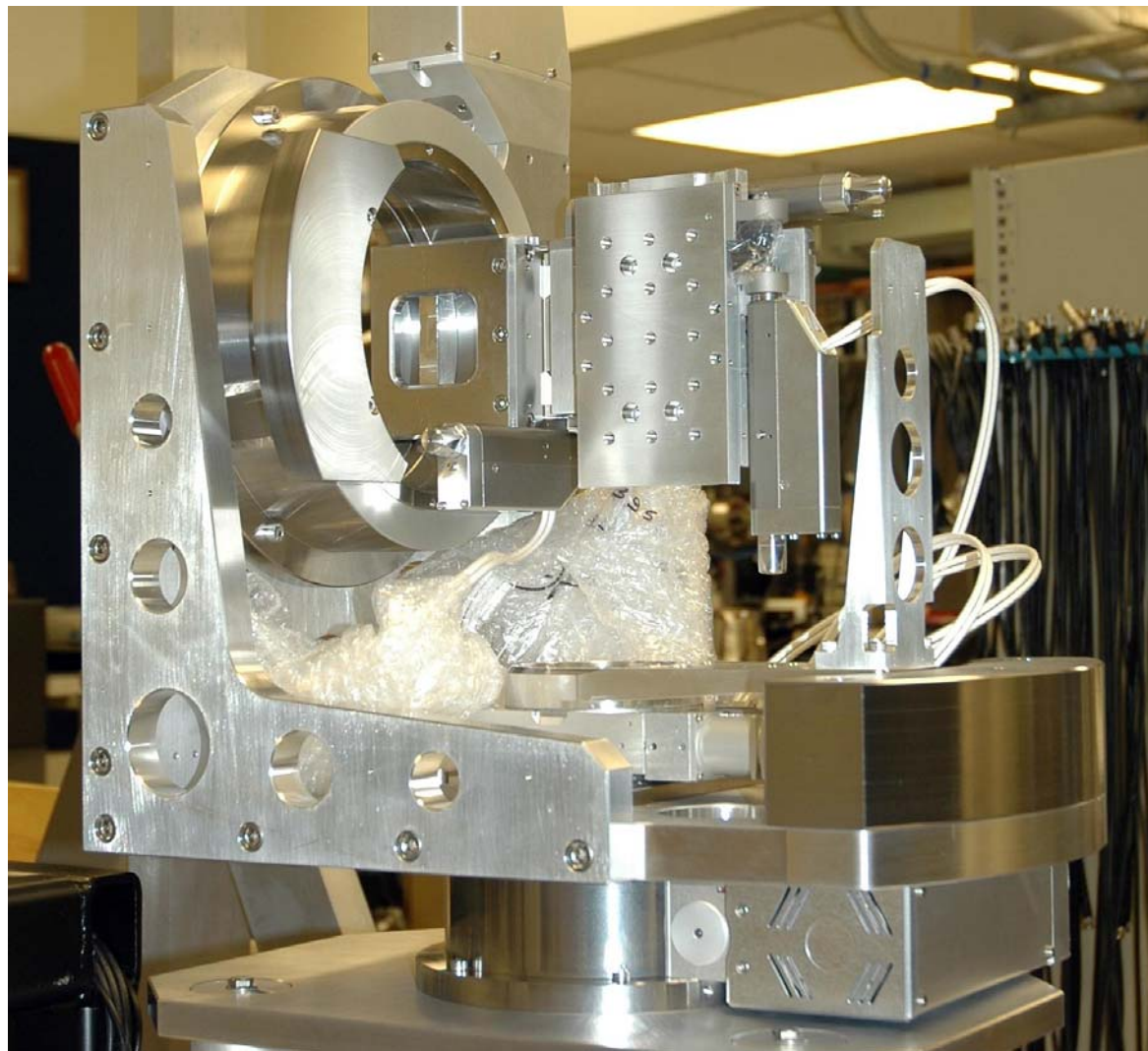


# Goniometer and main chamber



# Sample goniometer

- X-Y-Z axes
- 3 rotation axes
- Sample loading and heating in separate chamber



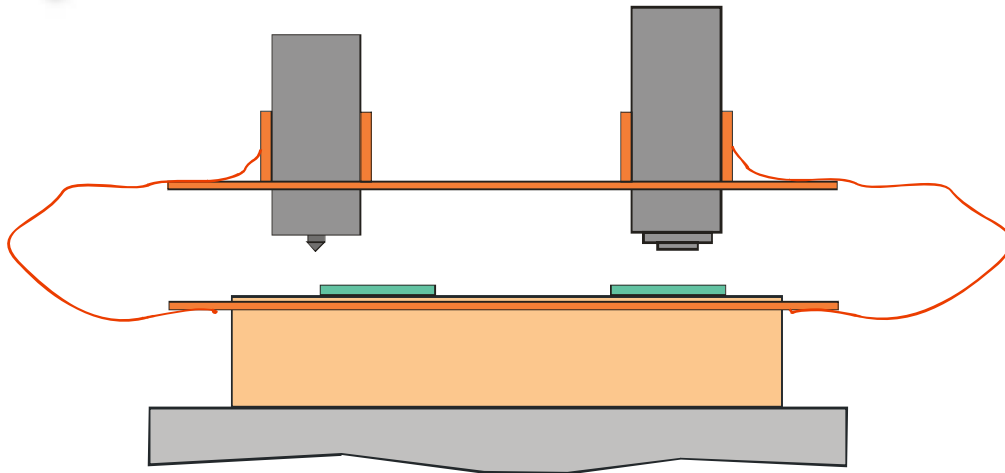


# Mechanical properties of tritiated films

---

- ◆ **Problem: Target film mechanical properties are important but largely unknown**
  - Need to nondestructively measure mechanical properties of tritiated films as they age.
  - Nanoscale mechanical properties are central to understanding early He release and film failure.
  - Separating thin film properties from the substrate is an additional complication requiring detailed modeling.
- ◆ **Applications:**
  - Track changes in mechanical strength as  $^3\text{He}$  increases and composition changes.
  - Study effects of alloying additions and impurities on strength.

# Nanoindentation of tritiated films



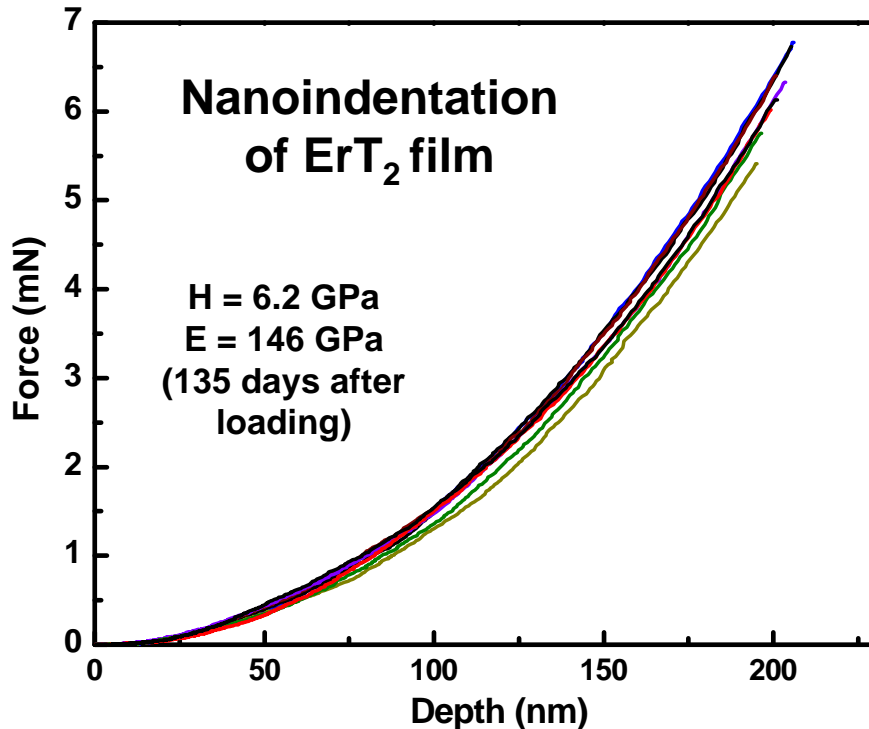
Sample containment fixturing

- Samples, indenter tip and optical microscope enclosed in a bag.
- Samples loaded and unloaded in 870.
- Tip and sample hardware dedicated to tritium usage.

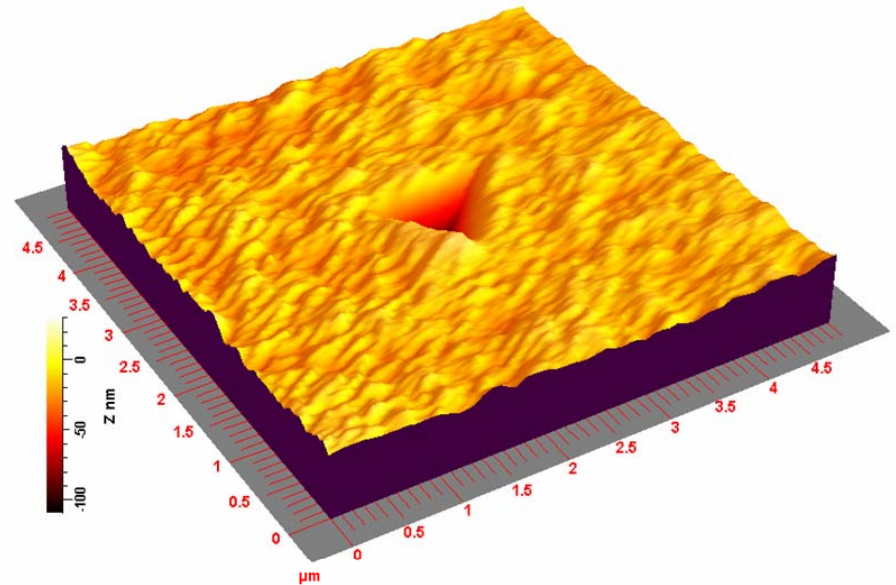


# Nanoindentation of Erbium Tritide

*Finite-Element modeling of force and stiffness determines film **hardness** and **Young's modulus**.*

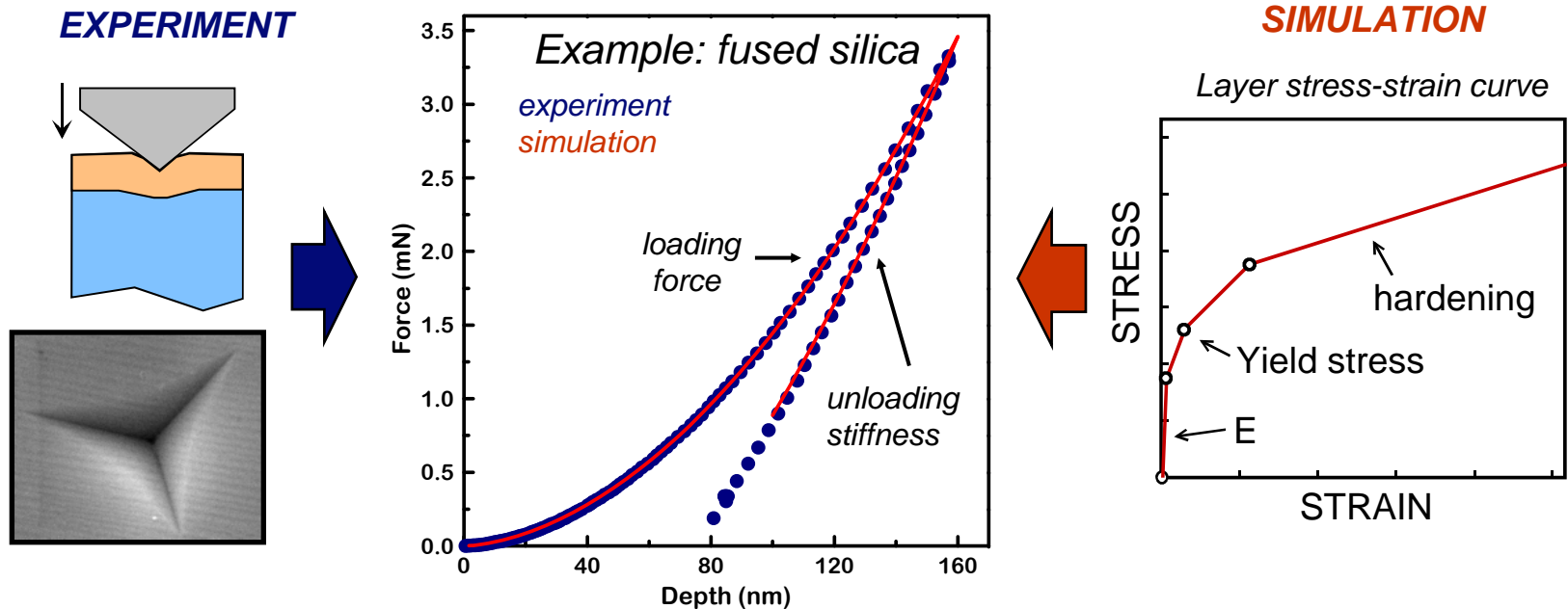


*In situ scan profiling of the residual indent may determine the **coefficient of work hardening**. (under development)*



**Residual indent profile and pileup imaged using the indenter tip and the new nano-positioning stage**

# Modeling of nanoindentation

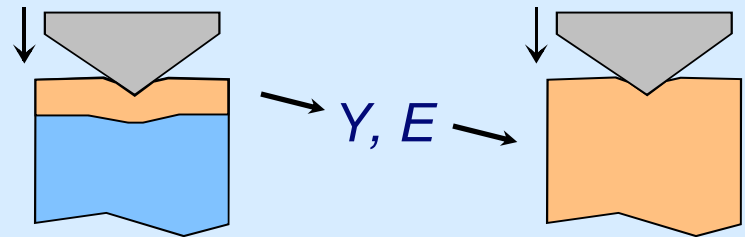


- **Experiment:** triangular tip pressed into specimen – force required depends on the mechanical properties of both layer and substrate.
- **Simulation:** finite element modeling – vary yield and elasticity for just the layer until a good fit to experiment is obtained.

# Finite-element simulations of nanoindentation

- ◆ Simulations use Abaqus/Standard 6.3 on a 450 MHz Sun workstation.
  - *2D: 30-60 mins.*
  - *3D: up to a few days.*
- ◆ Properties of the indenter and underlying layers and substrate are fixed at known values.
- ◆  $Y$  and  $E$  for the layer are varied until a good fit to experiment is obtained.
  - *Tip yielding, stress, friction are all modeled.*
- Two primary simplifications:
  - *2-dimensional axisymmetric meshes*
  - *isotropic elastic-plastic materials with Mises yield criteria*

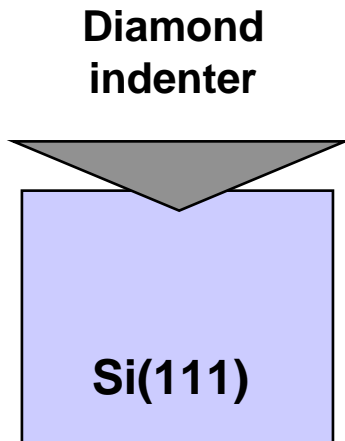
- Hardness of the layer material is determined by an additional simulation of a “bulk” sample of just the layer material:



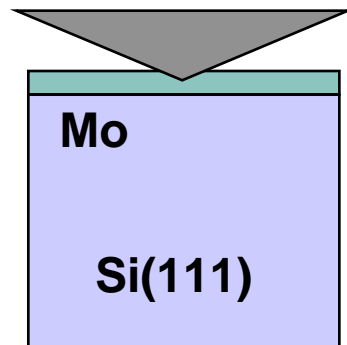


# Samples: $\text{ErD}_2$ and $\text{ErT}_2$ layers on Mo/Si

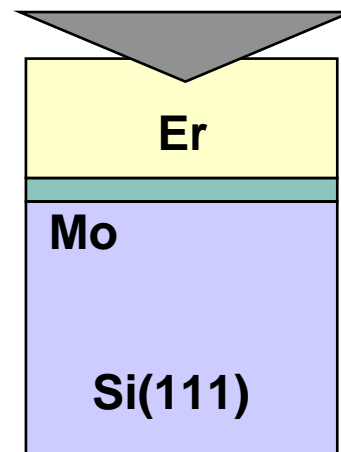
(1) Measured  
Si(111)  
substrate



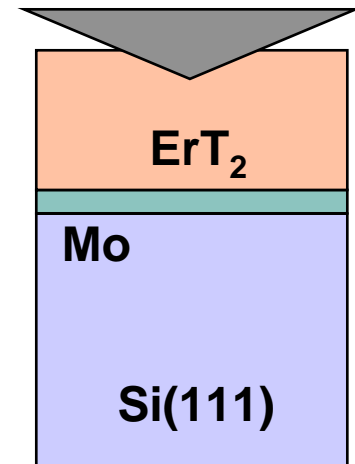
(2) Deposit 95  
nm Mo -  
measured  
properties



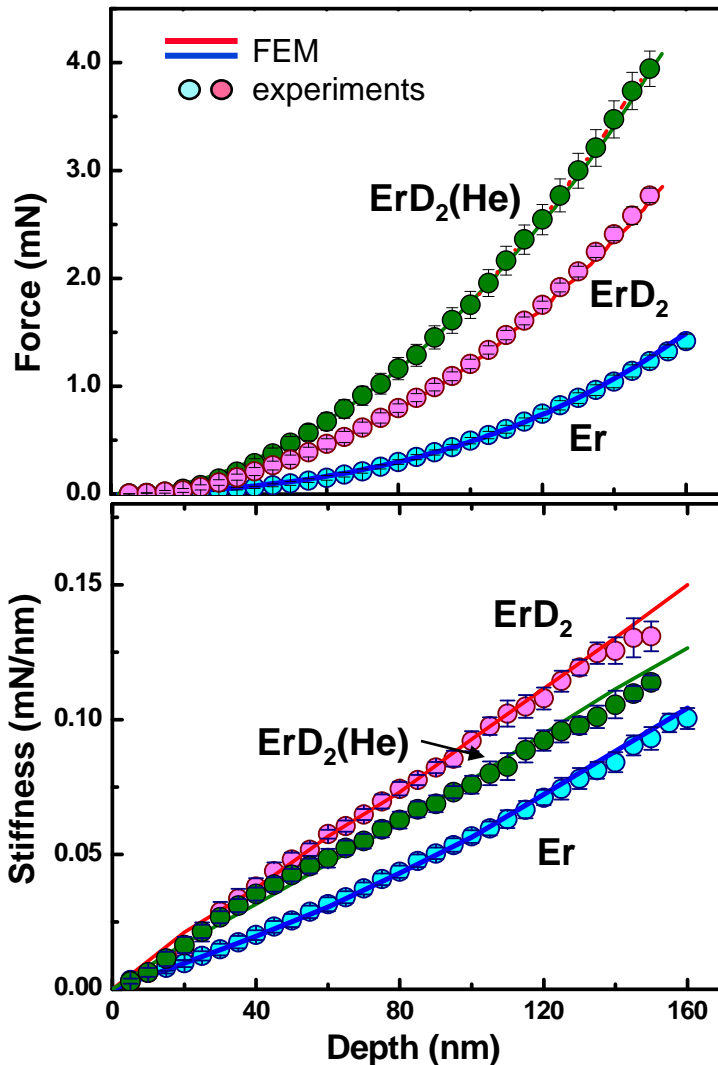
(3) Deposit  
500 nm Er -  
measured  
properties



(4) Load with D  
or T - measured  
properties



# Er, ErD<sub>2</sub> and ErD<sub>2</sub> implanted with 5% <sup>4</sup>He



Finite-element analysis

## Er layer on Mo/Si(111):

Y:  $0.15 \pm 0.04$  GPa

E:  $77 \pm 12$  GPa

H:  $1.9 \pm 0.4$  GPa

## ErD<sub>2</sub> layer on Mo/Si(111):

Y:  $1.53 \pm 0.19$  GPa

E:  $155 \pm 9$  GPa

H:  $4.5 \pm 0.4$  GPa

## ErD<sub>2</sub> layer implanted with He

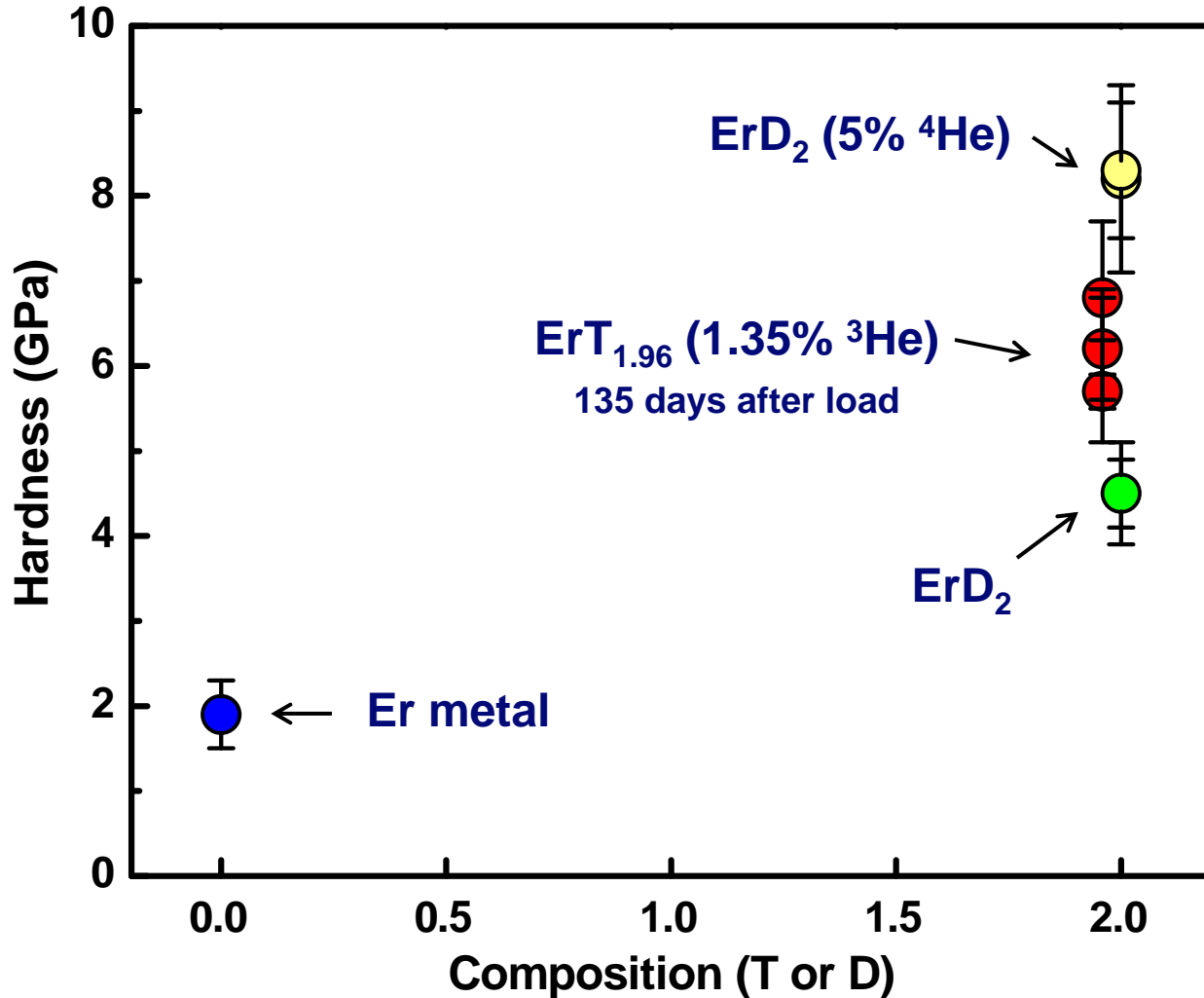
Y:  $3.32 \pm 0.41$  GPa

E:  $142 \pm 10$  GPa

H:  $8.3 \pm 0.8$  GPa

- ◆ Er layer is 2-3x harder and ~2x stiffer after loading with D
- ◆ Implanting 5% He further increases hardness ~2x

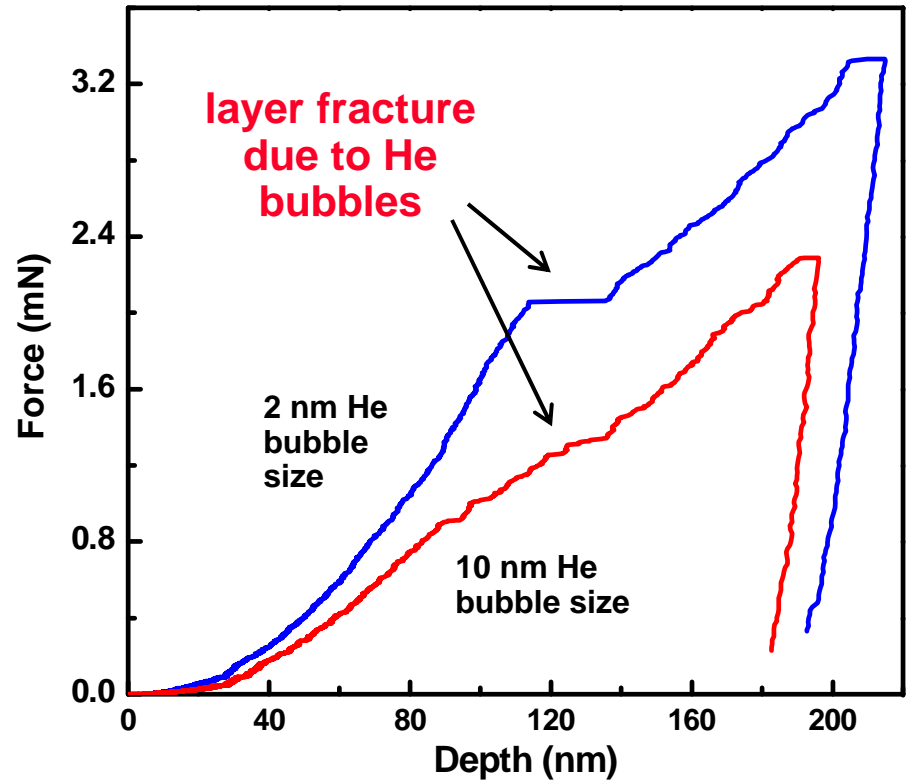
# Hardness vs. composition and He content



# He bubbles in Ni

## Nanoindentation of He-implanted Ni

- ◆ He bubbles strengthen the material, but are susceptible to failure in shear.





# Summary

---

- ◆ **Multi-element ion beam analysis system**
  - Simultaneous, non-destructive profiling of H, D, T,  $^3\text{He}$ , O, and surface C.
  
- ◆ **Nanoindentation of tritiated films**
  - Mechanical property measurements for tritiated thin films.